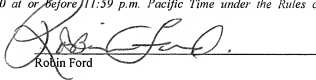


PATENT  
RESPONSE UNDER 37 CFR 1.116  
EXPEDITED PROCEDURE  
EXAMINING GROUP 1795

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

*I hereby certify that this correspondence is being electronically filed with the United States Patent and Trademark Office on February 3, 2010 at or before 11:59 p.m. Pacific Time under the Rules of 37 CFR § 1.8.*



Robin Ford

Appl No. : 10/587,194 Confirmation No. 8444  
Applicant : Jean-Louis Stehle  
Filed : July 24, 2006  
Title : PROTECTED PATTERN MASK FOR REFLECTION LITHOGRAPHY  
IN THE EXTREME UV OR SOFT X-RAY RANGE  
TC/A.U. : 1795  
Examiner : Jonathan G. Jelsma  
Docket No. : 58059/N75  
Customer No. : 23363

AMENDMENT AFTER FINAL ACTION

Mail Stop AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Post Office Box 7068  
Pasadena, CA 91109-7068  
February 3, 2010

Commissioner:

In response to the Office action of August 3, 2009, please amend the above-identified application as follows:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks/Arguments** begin on page 6 of this paper.